



511.36276VV3

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: S. TAI, et al.
Serial No.: 10/784,996
Filed: FEBRUARY 25, 2004
Title: PROCESS FOR PREPARING PHOSPHOR PATTERN FOR
FIELD EMISSION DISPLAY PANEL, PHOTOSENSITIVE
ELEMENT FOR FIELD EMISSION DISPLAY PANEL,
PHOSPHOR PATTERN FOR FIELD EMISSION DISPLAY
PANEL AND FIELD EMISSION DISPLAY PANEL
Group AU: 1756
Examiner: John A. McPherson
Confirm. No.: 9776

DECLARATION UNDER 37 CFR 1.132

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

We, Seiji TAI, Yoshiyuki HORIBE, Hiroyuki TANAKA, Takeshi NOJIRI,
Kazuya SATOU, Naoki KIMURA, and Mariko SHIMAMURA, each a citizen of Japan,
presently residing respectively at: 21-26, Suwa-cho 5-chome, Hitachi-shi, Ibaraki-
ken, Japan; 42-97, Ishinazaka-cho 1-chome, Hitachi-shi, Ibaraki-ken, Japan;
Byupare Mito, 3-3-702, Joto 2-chome, Mito-shi, Ibaraki-ken, Japan; Erudimu
Hirasaza 203, 3656-1, Shimogou, Iwama-cho, Nishi-ibaraki-gun, Ibaraki-ken, Japan;
5-A102, Naka-narusawa-cho 1-chome, Hitachi-shi, Ibaraki-ken, Japan; Namekawa-
ryo 304, 20-13, Higashi-namekawa-cho 1-chome, Hitachi-shi, Ibaraki-ken, Japan;
and Mutsumi-ryo 201, 14-10, Motomiya-cho 4-chome, Hitachi-shi, Ibaraki-ken, Japan,
DECLARE THAT:

1. We are the named inventors of the subject matter disclosed and claimed in Application No. 10/784,996, filed February 25, 2004 (hereinafter "above-identified application").
2. We are aware of the Office Action mailed June 28, 2005 in the above-identified application, and the rejection of claims 1 and 2 therein under 35 USC 102(e) as anticipated by the teachings of U.S. Patent No. 6,416,931, issued July 9, 2002.
3. We are further aware of the statements in Item 3 on page 4 of the Office Action mailed June 28, 2005, in the above-identified application, that U.S. Patent No. 6,416,931 discloses a photosensitive element comprising a support film, a thermoplastic resin layer (corresponding to the filling layer of the invention claimed in the above-identified application) on the support film, and a phosphor-containing photosensitive resin composition layer provided on the thermoplastic resin layer, wherein the phosphor-containing photosensitive resin layer comprises a film property imparting polymer, a photopolymerizable unsaturated compound having an ethylenic unsaturated group, a photopolymerization initiator which produces a free radical, and a phosphor, the Examiner pointing to column 101, line 53 to column 102, line 14 of U.S. Patent No. 6,416,931.
4. Insofar as the disclosure in U.S. Patent No. 6,416,931, including the description in column 101, line 53 to column 102, line 14, describes the subject matter of claims 1 and 2 of the above-identified application, this disclosure in U.S. Patent No. 6,416,913 describes inventions by the inventors named in the above-identified application, and not inventions of inventors named in U.S. Patent No. 6,416,931 and not named as inventors in the above-identified application.

5. We, as the inventors of subject matter disclosed in U.S. Patent No. 6,416,931 that describes the invention set forth in claims 1 and 2 of the above-identified application, disclosed this subject matter to the inventors named in U.S. Patent No. 6,416,931.

6. The inventorship of the subject matter claimed in claims 1 and 2 of the above-identified application is correct in that U.S. Patent No. 6,416,931 includes subject matter disclosed to the inventors named in U.S. Patent No. 6,416,931 and not named as inventors in the above-identified application, by inventors named in the above-identified application.

I hereby declare that all statement made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine, or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

June 6, 2006
Date

Sg Tai
Seiji TAI

May 31, 2006
Date

Yoshiyuki Horibe
Yoshiyuki HORIBE

May 30, 2006
Date

Hiroyuki Tanaka
Hiroyuki TANAKA

May 30, 2006
Date

Takeshi Nojiri
Takeshi NOJIRI

Jun. 5, 2006
Date

Kazuya Satou
Kazuya SATOU

Jun. 15, 2006
Date

Naoki Kimura
Naoki KIMURA

Jun. 9, 2006
Date

Mariko Shimamura
Mariko SHIMAMURA